

**AMENDMENTS TO THE CLAIMS**

Please **AMEND** claims 1-3, 5, 7, 9, and 12-15 as shown below.

This listing of claims will replace all prior versions, and listings, of claims in the application.

1. (Currently Amended) A method for fabricating a field emission display, comprising:
  - forming a cathode electrode on a substrate;
  - forming an emitter, comprising ~~having~~ a carbon-based material, on the cathode electrode;
  - depositing an emitter surface treatment agent on the substrate to cover the emitter after forming the emitter;
  - hardening the emitter surface treatment agent; and
  - removing the hardened emitter surface treatment agent from the substrate for exposing ~~such that the carbon-based material contained in the emitter can be exposed~~.
2. (Currently Amended) The method of claim 1, wherein the step of forming the emitter further comprises:
  - printing a paste, comprising ~~having~~ the carbon-based material, on the cathode electrode; and
  - heat-treating the printed paste at a temperature lower than a complete-baking temperature for the paste.

3. (Currently Amended) The method of claim 2, wherein the paste is printed by through-a screen-printing process using a metal mesh screen.
4. (Original) The method of claim 1, wherein the carbon-based material is selected from the group consisting of a carbon nanotube, graphite, and diamond.
5. (Currently Amended) The method of claim 1, wherein the emitter surface treatment agent is deposited by through-a spin-coating process.
6. (Original) The method of claim 1, wherein the emitter surface treatment agent is hardened by a heat-treatment process.
7. (Currently Amended) The method of claim 1, wherein the emitter surface treatment agent comprises is-a polyimide solution.
8. (Original) The method of claim 2, wherein the printed paste is heat-treated at the temperature of about 350-430°C for about 2 minutes.
9. (Currently Amended) The method of claim 6, wherein the heat-treatment process is performed in a state where comprises placing the substrate deposited with the surface treatment agent is located on a hot plate maintained ing at a temperature of about 90°C for about 20 minutes.
10. (Previously Presented) A method for forming a carbon-based emitter, comprising:  
forming an emitter including a carbon-based material;

forming a surface treatment agent over the emitter after forming the emitter;  
heating the surface treatment agent for forming a treatment film; and  
removing at least a portion of the treatment film.

11. (Previously Presented) The method of forming a carbon-based emitter of claim 10, wherein the carbon-based emitter is used in a field emission display.

12. (Currently Amended) The method of forming a carbon-based emitter of claim 10, wherein the surface treatment agent comprises ~~is~~ a polyimide solution.

13. (Currently Amended) The method of forming a carbon-based emitter of claim 10, wherein the heating of the surface treatment agent is to a temperature of about 90°C.

14. (Currently Amended) The method of forming a carbon-based emitter of claim 13, wherein the heating of the surface treatment agent is conducted for about 20 minutes.

15. (Currently Amended) The method of forming a carbon-based emitter of claim 10, wherein the carbon-based material includes at least one of a carbon-nanotube, graphite, and diamond.